Controlled self-organization of polymer nanopatterns over large areas

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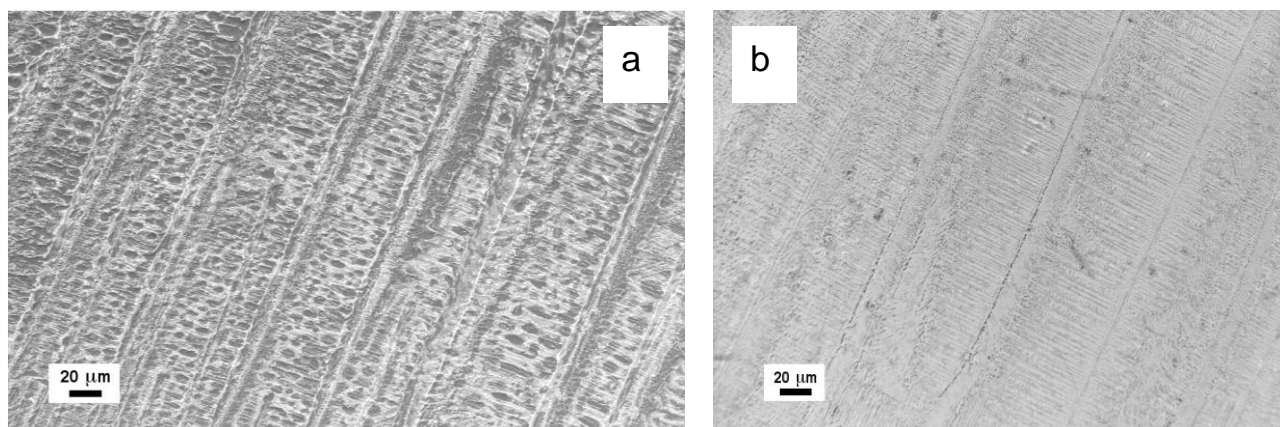*: email: afraleoni@units.it

Supporting Information

Figure S1 - a), b): SEM images of PMMA nanopatterns of type E, I, respectively, at low magnification.
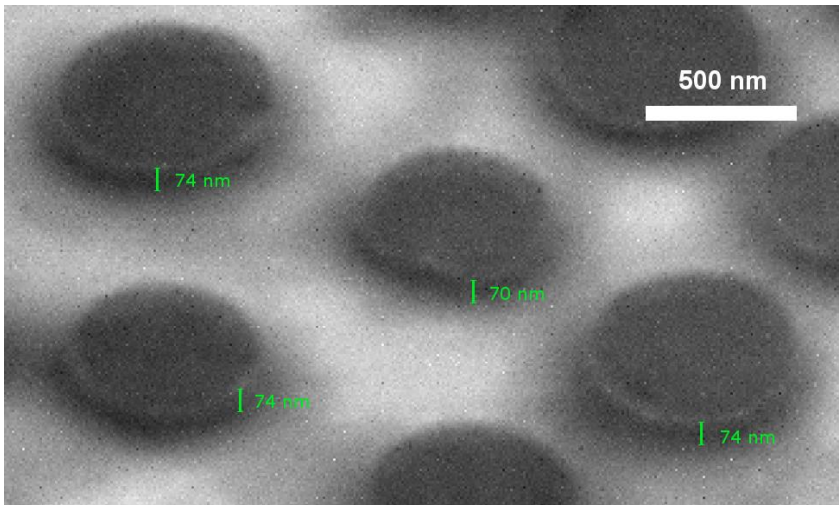
Figure S2 - SEM image of the type M patterns used as lithographic mask for the ICP-RIE treatment, evidencing the thickness of the patterns.